

IN THE SPECIFICATION

Paragraph at page 10, line 21:

Given the aim of photolithographic apparatus 10 as providing an optimal transmission medium path for irradiating a workpiece, e.g. a wafer, contained within pressure-tight workpiece cell 8 with a suitable photolithographic light source, cell cover 4 preferably comprises a transparent material selected for low light absorption characteristics. As shown by the cross-hatching in the drawing, the cell cover 4 is one-piece, unitary, and integral. In addition to providing the overhead boundary of workpiece cell 8, cell cover 4 further includes an upper surface 6 and sidewall members 3 mutually configured to define an open reservoir volume vertically bounded by the upper edges of sidewall members 3 and disposed in an overlapping manner over workpiece cell 8. As shown in the depicted embodiment, the open reservoir has a substantially planar bottom surface extending to or slightly beyond the edges of the workpiece cell 8 as defined by support members 15. The planar bottom surface of the open reservoir is preferably bounded at its peripheral edges by an indented gutter channel 16. It should be noted that while the depicted embodiment employs an open reservoir implementation, in the alternative, the reservoir supported by cell cover 4 may be enclosed or otherwise covered to prevent contaminants from entering an immersion fluid contained therein.